

ABSTRACT

A reflective mask blank 100 has a substrate 1; a multilayer reflective film 2 that reflects exposure light and that is provided on one main surface of the substrate 1; and an absorber film 5 provided above the multilayer reflective film 2. The absorber film 5 contains one or both of ruthenium (Ru) and platinum (Pt), and further contains one or both of carbon (C) and silicon (Si). A surface of the absorber film 5 has a root mean square roughness (Sq) of 0.40 nm or less.

Fig. 1